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FEB 2 1 2008

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors:

Jian Zhou; Hua Chu

Assignee:

Nanometrics Incorporated

Title:

Method for Automatically De-Skewing of Multiple Layer Wafer for

Improved Pattern Recognition

Application No.:

09/974,721

Filing Date:

October 9, 2001

Examiner:

Colin M. Larose

Group Art Unit:

1765

Docket No.:

NAN050 US

Confirmation No.:

7841

Saratoga, California February 21, 2008

Mail Stop Amendment Commissioner For Patents P.O. Box 1450 Alexandria, VA 22313-1450

RESPONSE TO OFFICE ACTION

Dear Sir:

This Response to Office Action is responsive to the November 21, 2007, Office Action, which has a statutorily shortened period for response that ends February 21, 2008. Please enter the following amendments before taking action on the merits of the above-referenced application.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.

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